

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 6,980,304 B2  
APPLICATION NO. : 10/802728  
DATED : December 27, 2005  
INVENTOR(S) : Oliver Broermann et al.

Page 1 of 2

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Claims 4-14 should read:

4. The method according to claim 1, wherein in the case of a plurality of parameters, the computing and control unit calculates one quality parameter the quality parameter representing the quality of the measurement from the calculated parameters, the quality parameter being compared with a prescribed quality limiting value, a warning signal being generated as a function of the comparison.
5. The method according to claim 3, wherein for the measuring step of the alignment, the measured data obtained in this measuring step includes a digital image, the computing rule for calculating the value of the relevant parameter includes the comparison of the digital image with a reference image.
6. The method according to claim 3, wherein for the measuring step of the detection of the at least one pattern, the measured data obtained includes a digital image, the computing rule for calculating the value of the relevant parameter includes the comparison of the digital image with a reference image.
7. The method according to claim 3, wherein for the measuring step of aligning the lens system, the measured data obtained includes a measuring curve, the computing rule for calculating the value of the parameter relating to the measuring step includes the comparison of the measuring curve with a reference curve.
8. The method according to claim 3, wherein the measuring step of the characteristic dimension is carried out with the aid of at least two measurements of the at least one pattern, the computing rule of the parameter relating to the pattern width measuring step includes the comparison of a first measuring curve of a first measurement with a second measuring curve of a second measurement.
9. The method according to claim 1, wherein the disc-shaped object is a semiconductor wafer, a mask, or a reticule or a flat panel display.
10. The method according to claim 1, wherein the measuring step is repeated for a multiplicity of disc-shaped objects, the value of the parameter for the respective measuring step is stored in a database, and a trend analysis is carried out for the parameter over the multiplicity of the respectively stored values.

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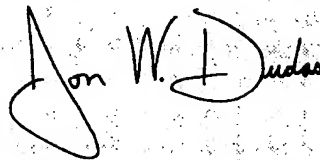
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11. The method according to claim 4, wherein for the measuring step of the alignment, the measured data obtained in this measuring step includes a digital image, the computing rule for calculating the value of the relevant parameter includes the comparison of the digital image with a reference image.
12. The method according to claim 4, wherein for the measuring step of the detection of the at least one pattern, the measured data obtained includes a digital image, the computing rule for calculating the value of the relevant parameter includes the comparison of the digital image with a reference image.
13. The method according to claim 4, wherein for the measuring step of aligning the lens system, the measured data obtained includes a measuring curve, the computing rule for calculating the value of the parameter relating to the measuring step includes the comparison of the measuring curve with a reference curve.
14. The method according to claim 4, wherein the measuring step of the characteristic dimension is carried out with the aid of at least two measurements of the at least one pattern, the computing rule of the parameter relating to the pattern width measuring step includes the comparison of a first measuring curve of a first measurement with a second measuring curve of a second measurement.

Signed and Sealed this

Twenty-seventh Day of February, 2007

A handwritten signature in black ink, appearing to read "Jon W. Dudas", is written over a faint, rectangular grid pattern.

JON W. DUDAS

*Director of the United States Patent and Trademark Office*